	L #	Search Text	DBs
1	L6	(438/763).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB
2	L7	(438/775).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB
3	L8	(438/786).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB
4	L9	(438/791).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB
5	L10	((tri adj2 silane) or trisilane or "Si.sub.3 H.sub.8")	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB
6	L11	silicon with (purge or remove) with (nitrid$6) with (purge or remove)	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB
7	L12	("ald" or (atomic adj2 layer))	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB
8	L13	((cycl$4 or cyclically) near5 deposition) or L12	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB
9	L24	257/E21.192	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB
10	L25	257/E21.267	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB
11	L26	257/E21.268	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB

	L #	Search Text	DBs
12	L27	257/E21.293	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB

	Ref #	Search Text
155	S6	S4 with ((tri adj2 silane) or trisilane)
156	S162	((tri adj2 silane) or trisilane)
157	S163	((tri adj2 silane) or trisilane or "Si.sub.3 H.sub.8")
158	S68	S66 same (S62 or S67)
159	S166	(S164 or S165)
160	S165	("ald" or (atomic adj2 layer))
161	S164	((cycl$4 or cyclically) near5 deposition)
162	S73	(((cycl$4 or cyclically) near5 deposition) or "cld")
163	S168	S165 or S167
164	S167	(((cycl$4 or cyclically) near5 deposition) or "cld")
165	S170	S169 same S168

	DBs
155	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB
156	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB
157	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB
158	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB
159	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB
160	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB
161	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB
162	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB
163	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB
164	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB
165	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB

	Ref #	Search Text
166	S173	S171 and S170
167	S171	uniform$3 same step
168	S169	silicon same S163
169	S174	silicon same S168
170	S172	S171 same S170
171	S175	S171 same S174
172	S114	(@ad<= "20020719") and S113
173	S176	(@ad<= "20020719" @rlad<= "20020719") and S175
174	S28	((tri adj2 silane) or trisilane or "Si.sub.3 H.sub.8") and (ammonia or "nh.sub.3") and S26
175	S46	silicon with (purge or remove) with (nitrid$6) with (purge or remove)
176	S62	((cycl$4 or cyclically) near5 deposition)

	DBs
166	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB
167	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB
168	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB
169	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB
170	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB
171	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB
172	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB
173	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB
174	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB
175	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB
176	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB